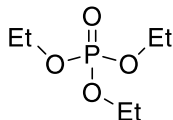


Catalog # 93-1559 Triethylphosphate, 99%



## Thermal Behavior:

- Melting point: -56.4°C
- Boiling point: 215°C

## Technical Notes:

1. Precursor and dopant used for thin phosphate films.

Target Deposit	Deposition Technique	Delivery Temperature	Pressure	Co-reactants	Deposition Temperature	Ref.
AlPO <sub>x</sub>	ALD	110°C	-	TMA	250°C	1
TiPO <sub>x</sub>	ALD	95°C	0.6 Torr	TiCl <sub>4</sub>	200°C	2
LiP <sub>x</sub> O <sub>y</sub> N <sub>z</sub>	CVD	50°C	10 Torr	Li(acac), NH <sub>3</sub>	450-575°C	3
P:SnO <sub>2</sub>	AA-CVD	MeOH Solution	-	BuSnCl <sub>3</sub> /MeOH	550°C	4
P:ZnO	CVD	MeOH Solution	-	Zn(OAc) <sub>2</sub> ·2H <sub>2</sub> O /MeOH	500°C	5

## References:

1. [ACS Appl. Mater. Interfaces, 2013, 5, 6161.](#)
2. [Adv. Mater. Interfaces 2018, 5, 1800423.](#)
3. [J. Power Sources, 2013, 244, 641.](#)
4. [Chem. Sci. 2018, 9, 7968.](#)
5. [RSC Adv. 2020, 10, 34527.](#)